EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S4	648	((wafer or semiconductor or substrate or workpiece) near5 (rotary or rotary or rotat$4 or spin or chuck)) and ((wafer or semiconductor or substrate or workpiece) near6 ("o ring" or seal$3 or gasket or barrier) near6 (bottom or underneath or beneath or below or lower or rear or backside)) and ((washing or clean$4 or decontaminat$4) near5 (wafer or semiconductor or substrate or workpiece))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/24 20:18
S15	293	((wafer or semiconductor or substrate or workpiece) near10 ((spincup or bath or dish or rotor or platen or chuck or cup or bowl or saucer or shroud or shell or deflector or shield) near4 (rotat$4 or rotary or spin$4 or turn$4))) and ((wafer or semiconductor or substrate or workpiece) near8 ("o ring" or seal$4 or bellows or shield or gasket or barrier) near8 (bottom or underneath or beneath or below or lower or rear$4 or backside or back)) and ((washing or clean$4 or decontaminat$4 or rins$4 or flushed or flushing) near5 (wafer or semiconductor or substrate or workpiece))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/25 07:20
S17	295	((wafer or semiconductor or substrate or workpiece) near10 ((spincup or bath or dish or rotor or platen or chuck or cup or bowl or saucer or shroud or shell or deflector or shield) near4 (rotat$4 or rotary or spin$4 or turn$4))) and ((wafer or semiconductor or substrate or workpiece) near8 ("o ring" or seal$4 or bellows or shield or gasket or barrier) near8 (bottom or underneath or beneath or below or lower or rear$4 or backside or back)) and ((washing or wash or clean$4 or decontaminat$4 or rins$4 or flushed or flushing) near5 (wafer or semiconductor or substrate or workpiece))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/25 07:57

S25	295	((wafer or semiconductor or substrate or workpiece) near10 ((spincup or bath or dish or rotor or platen or chuck or cup or bowl or saucer or shroud or shell or deflector or shield) near4 (rotat$4 or rotary or spin$4 or turn$4))) and ((wafer or semiconductor or substrate or workpiece) near8 ("o ring" or seal$4 or bellows or shield or gasket or barrier) near8 (bottom or underneath or beneath or below or lower or rear$4 or backside or back)) and ((washing or wash or clean$4 or decontaminat$4 or rins$4 or flushed or flushing) near5 (wafer or semiconductor or substrate or workpiece))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/25 09:04

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2464	134/902.CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/25 10:03

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S6	1488	134/148.ccls. or 134/153.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/25 10:03